

REMARKS

This application has been carefully reviewed in light of the Office Action dated December 3, 2008. Claims 1 to 7 are in the application, with Claims 1 and 5 being independent. Claims 1 and 5 have been amended herein. Reconsideration and further examination are respectfully requested.

Claims 1 to 3 were rejected under 35 U.S.C. § 103(a) over Analytica Chimica Acta, vol. 354, 1997, pp. 283-289 (Mlika). Claim 4 was rejected under 35 U.S.C. § 103(a) over Mlika in view of U.S. Patent No. 7,239,081 (Tsutsui). Claims 5 and 7 were rejected under 35 U.S.C. § 103(a) over Mlika in view of U.S. Patent No. 3,857,817 (Henshaw). Claim 6 was rejected under 35 U.S.C. § 103(a) over Mlika in view of Henshaw and further in view of U.S. Publication No. 2004/0129937 (Hirai). These rejections are respectfully traversed.

Claim 1 recites, *inter alia*, the insulating layer comprises a cured product of a phenol resin represented by formula (1).

Claim 5 recites, *inter alia*, coating a thermosetting composition containing at least a phenol resin represented by formula (1), and heating the thermosetting resin to form the insulating layer.

None of Mlika, Tsutsui, Henshaw, and Hirai, even in the proposed combinations, assuming, *arguendo*, that such could be combined, is seen to disclose or suggest at least the above-discussed features.

The Office Action takes the position that the calixarene film shown in Fig. 2a of Mlika corresponds to the claimed insulating layer. However, as Applicants understand it, the calixarene film is not an insulating layer. Rather, as described at p. 284,

sections 2.1.2 and 2.1.3, the insulating layer is SiO₂. Mlika discloses that calixarene is used as an ionophore in a microsensor. See p. 284, section 1, last paragraph. As such, it is Applicants' understanding that the calixarene film takes up a metal ion and functions as a semiconductor.

Tsutsui, Henshaw, and Hirai are not seen to remedy the foregoing deficiencies of Mlika.

The dependent claims are also submitted to be patentable because they set forth additional aspects of the present invention and are dependent from the independent claims discussed above. Therefore, separate and individual consideration of each dependent claim is respectfully requested.

No other matters being raised, the entire application is believed to be fully in condition for allowance, and such action is courteously solicited.

No fees are believed due; however, should it be determined that additional fees are required, the Director is hereby authorized to charge such fees to Deposit Account 06-1205.

Applicants' undersigned attorney may be reached in our Costa Mesa, California, office by telephone at (714) 540-8700. All correspondence should be directed to our address given below.

Respectfully submitted,

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